

Amendments to the Claims

This listing of claims will replace all prior versions and listings of claims in the application.

Listing of Claims:

1-10. (cancelled)

11. (currently amended) A filter for reducing non-uniformities in a plasma etching process, comprising:

a first region having a first non-zero transmittance; and

a second region having second non-zero transmittance that is different than said first non-zero transmittance level.

12. (original) The filter of claim 11, wherein said first region comprises a perimeter of said filter and said second region comprises a center portion of said filter.

13. (original) The filter of claim 12, wherein said first transmittance is lower than said second transmittance.

14. (original) The filter of claim 11, wherein said first region and said second region are eccentric.

15. (original) The filter of claim 11, wherein said second region is positioned to reduce transmission in areas where said plasma etching process experiences magnetic field

cusping.

16. (original) The filter of claim 11, wherein said filter comprises optical quality glass having a layer of metallic coating of a predetermined thickness.

17. (original) The filter of claim 11, wherein the thickness of said layer of metallic coating varies to form said first and said second regions.